



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/625,166
 Filing Date July 22, 2003
 Confirmation No. 8008
 Inventor Janos Fucsko et al.
 Assignee Micron Technology, Inc.
 Group Art Unit 2813
 Examiner Erik J. Kielin
 Attorney's Docket No. MI22-2246
 Customer No. 021567
 Title: Wet Etching Method of Removing Silicon From a Substrate (as Amended)

RESPONSE TO APRIL 18, 2005 OFFICE ACTION

To: Mail Stop Amendment
 Commissioner for Patents
 P. O. Box 1450
 Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From: Mark Matkin (Tel. 509-624-4276; Fax 509-838-3424)
 Wells St. John P.S.
 601 West First Avenue, Suite 1300
 Spokane, WA 99201-3828

Responsive to the Office Action dated April 18, 2005, Applicant amends and remarks as follows:

AMENDMENTS

Amendments to the Title

Please amend the title as follows:

WET ETCHING METHOD OF REMOVING SILICON
FROM A SUBSTRATE ~~AND METHOD OF FORMING~~
~~TRENCH ISOLATION~~